Exhibit R-2, RDT&E Budget Item Justification: PB 2014 Defense Advanced Research Projects Agency

APPROPRIATION/BUDGET ACTIVITY

R-1 ITEM NOMENCLATURE

0400: Research, Development, Test & Evaluation, Defense-Wide

PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES

DATE: April 2013

BA 3: Advanced Technology Development (ATD)

COST (\$ in Millions)	All Prior Years	FY 2012	FY 2013 [#]	FY 2014 Base	FY 2014 OCO ##	FY 2014 Total	FY 2015	FY 2016	FY 2017	FY 2018	Cost To Complete	Total Cost
Total Program Element	-	144.047	111.008	117.080	-	117.080	159.229	168.112	170.163	175.601	Continuing	Continuing
MT-12: MEMS AND INTEGRATED MICROSYSTEMS TECHNOLOGY	-	55.380	41.466	30.225	-	30.225	29.386	23.642	22.095	20.095	Continuing	Continuing
MT-15: MIXED TECHNOLOGY INTEGRATION	-	88.667	69.542	86.855	-	86.855	129.843	144.470	148.068	155.506	Continuing	Continuing

[#] FY 2013 Program is from the FY 2013 President's Budget, submitted February 2012

A. Mission Description and Budget Item Justification

The Advanced Electronics Technology program element is budgeted in the Advanced Technology Development Budget Activity because it seeks to design and demonstrate state-of-the-art manufacturing and processing technologies for the production of various electronics and microelectronic devices, sensor systems, actuators and gear drives that have military applications and potential commercial utility. Introduction of advanced product design capability and flexible, scalable manufacturing techniques will enable the commercial sector to rapidly and cost-effectively satisfy military requirements.

The MicroElectroMechanical Systems (MEMS) and Integrated Microsystems Technology project is a broad, cross-disciplinary initiative to merge computation and power generation with sensing and actuation to realize a new technology for both perceiving and controlling weapons systems and battlefield environments. MEMS applies the advantages of miniaturization, multiple components and integrated microelectronics to the design and construction of integrated electromechanical and electro-chemical-mechanical systems to address issues ranging from the scaling of devices and physical forces to new organization and control strategies for distributed, high-density arrays of sensor and actuator elements. The project will also address thermal management, navigation and positioning technology challenges.

The goal of the Mixed Technology Integration project is to leverage advanced microelectronics manufacturing infrastructure and DARPA component technologies developed in other projects to produce mixed-technology microsystems. These 'wristwatch size', low-cost, lightweight and low power microsystems will improve the battlefield awareness and security of the warfighter and the operational performance of military platforms. The chip assembly and packaging processes currently in use produce a high cost, high power, large volume and lower performance system. This program is focused on the monolithic integration of mixed technologies to form batch-fabricated, mixed technology microsystems 'on-a-single-chip' or an integrated and interconnected 'stack-of-chips'. The ability to integrate mixed technologies onto a single substrate will increase performance and reliability, while driving down size, weight, volume and cost.

PE 0603739E: *ADVANCED ELECTRONICS TECHNOLOGIES* Defense Advanced Research Projects Agency

UNCLASSIFIED
Page 1 of 16

R-1 Line #55

^{##} The FY 2014 OCO Request will be submitted at a later date

Exhibit R-2, RDT&E Budget Item Justification: PB 2014 Defense Advanced Research Projects Agency

APPROPRIATION/BUDGET ACTIVITY

R-1 ITEM NOMENCLATURE

0400: Research, Development, Test & Evaluation, Defense-Wide

PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES

DATE: April 2013

BA 3: Advanced Technology Development (ATD)

B. Program Change Summary (\$ in Millions)	FY 2012	FY 2013	FY 2014 Base	FY 2014 OCO	FY 2014 Total
Previous President's Budget	150.286	111.008	104.665	-	104.665
Current President's Budget	144.047	111.008	117.080	-	117.080
Total Adjustments	-6.239	0.000	12.415	-	12.415
 Congressional General Reductions 	0.000	0.000			
 Congressional Directed Reductions 	0.000	0.000			
 Congressional Rescissions 	0.000	0.000			
 Congressional Adds 	0.000	0.000			
 Congressional Directed Transfers 	0.000	0.000			
 Reprogrammings 	-2.143	0.000			
SBIR/STTR Transfer	-4.096	0.000			
 TotalOtherAdjustments 	-	-	12.415	-	12.415

Change Summary Explanation

FY 2012: Decrease reflects reductions for internal below threshold reprogrammings and the SBIR/STTR transfer.

FY 2014: Increase reflects expansion of laser and maskless lithography work in Project MT-15.

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APPROPRIATION/BUDGET AC	TIVITY				R-1 ITEM I	NOMENCL	ATURE		PROJECT			
0400: Research, Development,	Test & Evalua	ation, Defen	se-Wide		PE 060373	39E: <i>ADVAN</i>	ICED ELEC	CTRONICS	MT-12: <i>ME</i>	EMS AND II	NTEGRATE	D
BA 3: Advanced Technology Dev	velopment (A	NTD)			TECHNOL	OGIES			MICROSY	STEMS TE	CHNOLOG	Y
COST (\$ in Millions)	All Prior		#	FY 2014	FY 2014	FY 2014					Cost To	Total
(,	Years	FY 2012	FY 2013 [#]	Base	oco##	Total	FY 2015	FY 2016	FY 2017	FY 2018	Complete	Cost
MT-12: <i>MEMS</i>	_	55.380	41.466	30.225	_	30.225	29.386	23.642	22.095	20.095	Continuing	Continuing
AND INTEGRATED												
MICROSYSTEMS												
TECHNOLOGY												

^{*}FY 2013 Program is from the FY 2013 President's Budget, submitted February 2012

Exhibit R-2A RDT&E Project Justification: PB 2014 Defense Advanced Research Projects Agency

A. Mission Description and Budget Item Justification

The MicroElectroMechanical Systems (MEMS) and Integrated Microsystems Technology program is a broad, cross-disciplinary initiative to merge computation and power generation with sensing and actuation to realize a new technology for both perceiving and controlling weapons systems and battlefield environments. Using fabrication processes and materials similar to those used to make microelectronic devices, MEMS applies the advantages of miniaturization, multiple components and integrated microelectronics to the design and construction of integrated electromechanical and electro-chemical-mechanical systems. The MEMS program addresses issues ranging from the scaling of devices and physical forces to new organization and control strategies for distributed, high-density arrays of sensor and actuator elements. These issues include microscale power and actuation systems as well as microscale components that survive harsh environments. The microfluidic molecular systems effort will develop automated microsystems that integrate biochemical fluid handling capability along with electronics, optoelectronics and chip-based reaction and detection modules for tailored sequence analysis to monitor environmental conditions, health hazards and physiological states. Thermal management technologies will develop heat resistant thermal layers to provide efficient operation for cooling electronic devices. Another focus in micro technologies is to improve navigation, position and timing capabilities for uncompromised navigation and positioning in today's dynamic military field of operations.

The major technical focus areas of the MEMS and Integrated Microsystems programs contained in this project are: 1) inertial measurement; 2) fluid sensing and control; 3) electromagnetic and optical beam steering; 4) chemical reactions on chip; 5) electromechanical signal processing; 6) analytical instruments; 7) thermal management; and 8) navigation and positioning technologies.

B. Accomplishments/Planned Programs (\$ in Millions)	FY 2012	FY 2013	FY 2014
Title: Micro-Technology for Positioning, Navigation, and Timing (Micro PN&T)	41.989	41.466	30.225
Description: The Micro-Technology for Positioning, Navigation, and Timing (Micro PN&T) program is developing technology for self-contained chip-scale inertial navigation and precision guidance. This technology promises to effectively mitigate dependence on Global Positioning System (GPS) or any other external signals, and enable uncompromised navigation and guidance capabilities. The program will enable positioning, navigation and timing functions without the need for external information updates by employing on-chip calibration, thereby overcoming vulnerabilities which arise in environments where external updates are not available such as caves, tunnels, or dense urban locations. The technologies developed will enable small, low-power, micro-gyroscopes capable of operating in both moderate and challenging dynamic environments; chip-scale primary atomic clock			

PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES Defense Advanced Research Projects Agency

DATE: April 2013

^{##} The FY 2014 OCO Request will be submitted at a later date

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ced Research Projects Agency		DATE:	April 2013		
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD)	R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES					
B. Accomplishments/Planned Programs (\$ in Millions)		FY	2012	FY 2013	FY 2014	
standards; and on-chip calibration systems for error correction. Advance containing all the necessary devices (clocks, accelerometers, gyroscope into a volume the size of a sugar cube. The small size, weight and power into a single package responds to the needs of guided munitions, unmanger The Micro PN&T program is an aggregation of Integrated Primary Atom Gyroscopes, Micro Inertial Navigation Technology, Information Tethered Rate Integrating Gyroscopes, Single-Chip Timing and Inertial Measuren Layer, and Chip-Scale Combinatorial Atomic Navigator. The technology DoD transition partnerships with the Services.	es, and calibration mechanisms) to be incorporated for (SWaP) of these technologies and their integration nned aerial vehicles (UAVs) and individual soldiers. ic Clock, Navigation Grade Integrated Micromachined Microscale Autonomous Rotary Stages, Micromachinent Unit, Primary and Secondary Calibration on Activation	d ined ve				
To achieve the low SWaP necessary for guided munitions, UAVs, and p the MicroPN&T program will have to push the limitations of integration a systems (MEMS) technologies. Unprecedented levels of precision will be environment. New architectures for devices will be developed that will be increase stability and performance of a MEMS structure. Applied resea ELT-01.	and performance in current MicroElectroMechanical be required to meet the stringent demands of the milit everage advances in fabrication techniques in order t	o				
FY 2012 Accomplishments: - Fabricated, for the first time, millimeter-sized 3D structures - spheres, low-cost, small size rate integrating gyroscopes; the design paradigm to velocity. - Identified fabrication method to co-fabricate clocks and inertial sensor microsystems through multi-layer packaging of inertial sensors, clocks at - Demonstrated three-dimensional microfabrication techniques of non-timetallic glass) for rate integrating gyroscopes that are compatible with lateral completed independent government evaluation of micro inertial navig military/residential neighborhood. Demonstrated boot-mounted inertial stesting. - Demonstrated a fabrication technique that allows for the integration of package.	o provide direct measurement of orientation and angulars into a ten cubic millimeter package for navigation and environmental isolation. raditional MEMS materials (e.g. diamond, fused silical arge-scale manufacturing. y 17 ns after one day of operation. ration technology in a closed-loop (700 m x 800 m), sensors with 16 m accumulated error after 4 hours of	ar , bulk				
FY 2013 Plans: - Demonstrate a microsystem rate-integrating gyroscope to provide dire	ectly measured orientation angle and angular velocity					

PE 0603739E: *ADVANCED ELECTRONICS TECHNOLOGIES* Defense Advanced Research Projects Agency

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Page 4 of 16 R-1 Line #55

	UNCLASSIFIED				
Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ed Research Projects Agency	DATE:	April 2013		
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD) R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS MT-12: MEMS AND INTEGRATED MICROSYSTEMS TECHNOLOGY					
B. Accomplishments/Planned Programs (\$ in Millions)		FY 2012	FY 2013	FY 2014	
 Demonstrate a fabrication technique to manufacture microsystem rate increase the level of performance by a factor of ten. Demonstrate a microsystem that combines a functional timing and iner. Demonstrate the co-fabrication of an inertial sensor and a calibration son the same stage. Model internal and external sources of error, scale-factor, and bias drif. Identify self-calibration techniques to compensate for long-term drift. Demonstrate small primary atomic/ion clocks with time losses of only 1 	rtial measurement unit in a ten cubic millimeter package. tage to enable integration of error correction technologies ft for inertial devices.				
 FY 2014 Plans: Demonstrate a microsystem rate-integrating gyroscope with performar Demonstrate a microsystem that combines a functional timing and iner loss of 1 ns/min and Circular Error Probable CEP < 10 m. Use models for internal and external sources of error to develop on-ch Develop architecture for chip-scale combinatorial atomic navigator. Demonstrate combinatorial physics for compact systems with a startup physics-based inertial devices. 	rtial measurement unit with performance values for time ip calibration algorithms.				
Title: Thermal Management Technologies (TMT)		13.391	0.000	0.000	
Description: The goal of the Thermal Management Technologies (TMT) nanostructured materials and other recent advances for use in thermal news to insert breakthrough materials and structures at all layers of DoD sperformance, and improved efficiency. Modern, high-performance heat to replace the copper alloy spreaders in conventional systems. Enhancing resistance through the heat sink to the ambient, increasing convection the conductivity, optimizing and/or redesigning the complementary heat sink blower) coefficient of performance was another thrust of this program. And structures that can provide significant reductions in the thermal resist of an electronic device and the next layer of the package, which might be through DoD industrial firms into future DoD systems.	nanagement systems. The overall goal of the program systems, and enable higher power densities, increased spreaders, which use two-phase cooling, were developed ng air-cooled exchangers by reducing the thermal blower, and increasing the overall system (heat sink and another element of this effort focused on novel materials stance of the thermal interface layer between the backsid				
FY 2012 Accomplishments: - Inserted Thermal Ground Plane substrates to demonstrate improveme transmit/receive modules, high-density electronic systems, avionics mod flexible, highly-conductive heat spreaders.					

APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD)	PE 0603739E: ADVANCED ELECTRONICS		-		
B. Accomplishments/Planned Programs (\$ in Millions)	F	Y 2012	FY 2013	FY 2014	
- Completed multiple insertion demonstrations for enhanced heat exchangers	, and initiated transitions to platforms.				
- Demonstrated 10x improvements over state of the art for re-workable therma	al interface materials.				
- Demonstrated high heat density active cooling modules for efficient operatio					
- Initiated development of near junction thermal transport techniques including	high thermal conductivity diamond and microfl	uidic			

Accomplishments/Planned Programs Subtotals

C. Other Program Funding Summary (\$ in Millions)

N/A

cooling.

Remarks

D. Acquisition Strategy

N/A

E. Performance Metrics

Specific programmatic performance metrics are listed above in the program accomplishments and plans section.

Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advanced Research Projects Agency

PE 0603739E: *ADVANCED ELECTRONICS TECHNOLOGIES* Defense Advanced Research Projects Agency

DATE: April 2013

55.380

41.466

30.225

Exhibit R-2A, RDT&E Project Ju	stification:	PB 2014 D	Defense Adv	anced Res	earch Proje	cts Agency				DATE: Apr	il 2013	
APPROPRIATION/BUDGET ACT 0400: Research, Development, Te	est & Evalua		se-Wide		PE 060373		_	PROJECT ECTRONICS MT-15: MIXED TECHNOLOGY INTEGRATION				
BA 3: Advanced Technology Deve	elopment (A	TD)			TECHNOL	.OGIES			INTEGRAT	TION		
COST (\$ in Millions)	All Prior Years	FY 2012	FY 2013 [#]	FY 2014 Base	FY 2014 OCO ##	FY 2014 Total	FY 2015	FY 2016	FY 2017	FY 2018	Cost To Complete	Total Cost
MT-15: MIXED TECHNOLOGY	-	88.667	69.542	86.855	-	86.855	129.843	144.470	148.068	155.506	Continuing	Continuing

^{*}FY 2013 Program is from the FY 2013 President's Budget, submitted February 2012

A. Mission Description and Budget Item Justification

The goal of the Mixed Technology Integration project is to leverage advanced microelectronics manufacturing infrastructure and DARPA component technologies developed in other projects to produce mixed-technology microsystems. These 'wristwatch size', low-cost, lightweight and low power microsystems will improve the battlefield awareness, security of the warfighter and the operational performance of military platforms. At the present time, systems are fabricated by assembling a number of mixed-technology components: microelectromechanical systems (MEMS), microphotonics, microfluidics and millimeterwave/microwave. Each technology usually requires a different level of integration, occupies a separate silicon chip and requires off-chip wiring, and requires fastening and packaging to form a module. The chip assembly and packaging processes produce a high cost, high power, large volume and lower performance system. This program is focused on the monolithic integration of mixed technologies to form batch-fabricated, mixed technology microsystems 'on-a-single-chip' or an integrated and interconnected 'stack-of-chips'.

The field of microelectronics incorporates micrometer/nanometer scale integration and is the most highly integrated, low-cost and high-impact technology to date. Microelectronics technology has produced the microcomputer-chip that enabled or supported the revolutions in computers, networking and communication. This program extends the microelectronics paradigm to include the integration of heterogeneous or mixed technologies. This new paradigm will create a new class of 'matchbook-size', highly integrated device and microsystem architectures. Examples of component-microsystems include low-power, small-volume, lightweight, microsensors, microrobots and microcommunication systems that will improve and expand the performance of the warfighter, military platforms, munitions and Unmanned Air Vehicles (UAVs).

The program includes the integration of mixed materials on generic substrates including glass, polymers and silicon. The program is design and process intensive, using 'standard' processes and developing new semiconductor-like processes and technologies that support the integration of mixed-technologies at the micrometer/nanometer scale. The program includes the development of micrometer/nanometer scale isolation, contacts, interconnects and 'multiple-chip-scale' packaging for electronic, mechanical, fluidic, photonic and rf/mmwave/microwave technologies. For example, a mixed-technology microsystem using integrated microfluidics, MEMS, microphotonics, microelectronics and microwave components could provide a highly integrated, portable analytical instrument to monitor the battlefield environment, the physical condition of a warfighter, the identity of warfighters (friend or foe) or the combat readiness of equipment. The ability to integrate mixed technologies onto a single substrate will drive down the size, weight, volume, and cost of weapon systems while increasing their performance and reliability.

B. Accomplishments/Planned Programs (\$ in Millions)	FY 2012	FY 2013	FY 2014
Title: Low Cost Thermal Imager - Manufacturing (LCTI-M)	21.300	20.509	19.000

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ed Research Projects Agency	DATE:	April 2013	
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD)	PE 0603739E: ADVANCED ELECTRONICS MT-	JECT 5: MIXED TE GRATION	CHNOLOGY	
B. Accomplishments/Planned Programs (\$ in Millions)		FY 2012	FY 2013	FY 2014
Description: The Low Cost Thermal Imager - Manufacturing (LCTI-M) eff work and will develop a pocket-sized, manufacturable, and practical therm provided to large numbers of warfighters. Availability of very low cost and new techniques and applications that could provide the decisive edge ner a soldier to have practical thermal imaging capability for locating warm of size, weight and power (SWaP) thermal camera will be integrated with a capability for tactical intelligence, surveillance and reconnaissance. In or in low-cost thermal imagers manufactured using wafer scale integration, processing. By the end of the program, the imager chips will be fully inter will have wireless connectivity to integrate video display with cell phones (SSL), PM Optics USMC, USSOCOM and industry will be the transition processing and reviewed camera design and overall architecture composition of the program of the p	mal imager at a price point that allows them to be d small form-factor infrared (IR) cameras will facilitate eded in modern battlefields. These cameras will allow ojects (e.g., enemy combatants) in darkness. The small handheld device such as a cell phone with network eder to achieve this goal, breakthroughs will be required vacuum packaging, low cost optics and low-power signal grated with a low-cost processor and optics. The camera or PDAs. U.S. Army PEO Soldier Sensors and Lasers partners.			
cost manufacturing infrastructure. - Demonstrated small pixel microbolometer producibility and performanc goal is achievable. - Initiated wafer level vacuum packaging development by establishing terseal tests showed good metal ring formation with good binding strength. - Demonstrated feasibility of wafer scale optics producibility. - Built prototype wafer scale optics for 320x240, 17 micrometer pixel arraperformed.	e. Preliminary results indicated detector performance chnical approach and material selection criteria. First			
FY 2013 Plans: - Establish interim small form-factor camera integration. - Demonstrate and deliver interim 640x480 LCTI-M camera. - Finalize design of low cost IR optics for LCTI-M. - Conduct 2nd LCTI-M program review and plan technology transition. - Demonstrate an integrated smart phone and first prototype thermal camera.	nera.			
FY 2014 Plans: - Fabricate low cost wafer scale optics for LCTI-M camera Demonstrate small form factor camera integration employing 3-D asser	mbly techniques.			

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advanced	Research Projects Agency	DATE: /	April 2013	
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD) R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES NT-15: MIXED TECHNOLOGY INTEGRATION				
B. Accomplishments/Planned Programs (\$ in Millions) - Deliver final 640x480 LCTI-M cameras with test results and 1280X1024	camera engines	FY 2012	FY 2013	FY 2014
Title: Maskless Direct-Write Nanolithography for Defense Applications		10.834	15.000	0.000
Description: The Maskless Direct-Write Nanolithography for Defense App lithography tool that will address both DoDs needs for affordable, high perf commercial market's need for highly customized, application-specific ICs. manufacturing technology for low volume nanoelectromechanical system (Transition will be achieved by maskless lithography tools, installed in the Tenable affordable incorporation of state-of-the-art semiconductor devices in upgrade of legacy military systems.	ormance, Integrated Circuits (ICs) in small lots and the In addition, this program will provide a cost effective NEMS) and nanophotonic devices within the DoD. rusted Foundry and in commercial foundries, which will			
FY 2012 Accomplishments: - Finalized system and subsystem requirements for the lithography demonent Designed an optical system which will exhibit patterning performance to a Successfully integrated the 3rd generation electron beam column with a Demonstrated a dynamic pattern generator with electron reflection efficient Demonstrated complex pattern printing in photo sensitive material using achieving a resolution of 75 nm with a wafer-plane current of 200 nano am Developed a new process to fabricate the electron-focusing lenslets and will eliminate several failure mechanisms and greatly increase the reliability - Qualified a chemically-amplified resist for patterning with the 3rd generate	the 14 nm node at 11 wafer-levelper-hour-per-column. Rotary Stage Demonstrator Platform. ency in excess of 50%. a fully programmable dynamic pattern generator, ps. CMOS shift registers in concert at one location, which y of dynamic pattern generator fabrication.			
FY 2013 Plans: - Design and build a 4th generation electron-beam column capable of 14 r - Demonstrate system-level lithography for at least 3 relevant patterns obtacritical dimension uniformity, line edge roughness, and layer-to-layer overlayer geometry half pitch of ~ 32 nm). Throughput will be 1 wafer-level-per from 0.7-4.2 microamps.	nm node lithography. ained from an industry partner achieving resolution, ay tolerance compatible with the 14 nm node (metal			
Title: RESOLVE		0.000	0.000	15.000
Description: The goal of RESOLVE is to extend the capability of the Mask direct-write lithography tool capable of affordable fabrication of custom ASI Foundry. In addition, this program will provide a manufacturing technology nanophotonics initiatives within the DoD. It is expected that this tool will pr	CS down to nodes required by the DoD in the Trusted of for nanoelectromechanical systems (NEMS) and			

PE 0603739E: *ADVANCED ELECTRONICS TECHNOLOGIES* Defense Advanced Research Projects Agency

R-1 Line #55

	UNCLASSIFIED					
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APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD)	R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES	PROJEC MT-15: M INTEGRA	MIXED TECHNOLOGY			
B. Accomplishments/Planned Programs (\$ in Millions)		F	Y 2012	FY 2013	FY 2014	
lithography for fabrication of deep-sub-micron complementary metal-oxi also meet the objectives required in the commercial sector for high-volu		d to				
 FY 2014 Plans: Ship a pre-alpha reflection e-beam lithography tool (developed under for evaluation and process development. Demonstration at the Trusted Foundry of all patterning specifications to Develop new compact electron-beam column for integration into 6-col tool. 	for advanced nodes derived by an industry partner.					
Title: Excalibur			15.642	18.420	0.000	
Description: The Excalibur program will develop high-power electronical powered by a fiber laser amplifier. These fiber-laser arrays will be suffice be fielded on a variety of platforms with minimal impact on the platform's possess an adaptive-optic capability to minimize beam divergence in the field-of-view beam steering for target tracking. With each Excalibur array (at up to 3 kilowatts (kW) per amplifier), high power air-to-air and air-to-ginfeasible because of laser system size and weight. In addition, this prolasers which will provide an alternate route to efficiently reaching mission scalability of the optical phased array architecture. Excalibur arrays will power by adding additional elements to the array. Excalibur will provide airborne platforms, including all aircraft flying at altitudes below 50,000 fiman-portable air-defense systems (MANPADS) and more capable air-to-excalibur will enable these platforms to fly at lower altitude and conduct as reconnaissance despite low-lying cloud cover. Further capabilities midentification, tracking, designation, precision defeat with minimal collated. The Excalibur program will also develop efficient high-power laser amplifier arrays will be designed to work in tandem with the core laser of PE 0602702E, Project TT-06. In addition a conceptual design and CON Measure (HELCM) system will be developed to enable a near-term capathis technology will transition via industry.	ciently lightweight, compact, and electrically efficient to so original mission capabilities. Each array element will be presence of atmospheric turbulence, together with vary element powered by high power fiber laser amplifier ground engagements will be enabled that were previously as will also develop kilowatt-class arrays of diode in-relevant power levels, and they will test the ultimate be conformal to aircraft surfaces and scalable in size the technology foundation for defense of next general fit, against proliferated, deployed, and next-generation poair missiles converted for use as ground-to-air missiles truly persistent, all-weather ground missions, such may include multichannel laser communications, target eral effects as well as other applications. If a gray based on coherent or spectral beamles (100 kilowatt class) will be investigated. These lase components developed under the Excalibur program in IOPS development for a High Energy Laser Counter	II vide- rs usly e and eation les.				

Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ced Research Projects Agency	DATE:	April 2013		
APPROPRIATION/BUDGET ACTIVITY	R-1 ITEM NOMENCLATURE	PROJECT			
0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD) PE 0603739E: ADVANCED ELECTRONICS M TECHNOLOGIES		MT-15: MIXED TECHNOLOGY INTEGRATION			
B. Accomplishments/Planned Programs (\$ in Millions)		FY 2012	FY 2013	FY 2014	
FY 2012 Accomplishments: - Completed the design, fabrication and procurement of the component array elements, each fed by a compact 1-kW fiber laser amplifier. - Achieved a record 1.93 kW coherent laser combining using a diffraction beam quality. - Demonstrated phase locking of a 7 element array over a 7 km outdoor. - Coherently combined 7 high-power fiber lasers in an optical phased a beam quality. - Initiated development of ancillary HELCM open architecture subsystelightweight pod).	ve optical element with 79% efficiency and near-perfector range in turbulent conditions. Array with a total output power of 2.5 kW and near-perfectors.	ect			
 FY 2013 Plans: Demonstrate beam combining (coherent or spectral) of twenty-one 1- Demonstrate coherent combining of a 19-element 2-D optical phased optics. Conduct field measurements to assess the potential of a conceptual process. 	array with a combined power of 21 kW and tip/tilt ada	ptive			
Title: Endurance	, ,	0.000	6.500	22.80	
Description: The Endurance program will develop technology for pod-from emerging and legacy electro-optical IR guided surface-to-air missi and test ancillary subsystems, such as a command subsystem, a threat framework, subsystem interfaces, and the design, integration, and testi. This program is an early application of technology developed in the Excresearch for this program is budgeted in PE 0602702E, project TT-06.	les. The focus of the Endurance effort will be to develor t missile warning subsystem, a mechanical support ng of a form/fit/function brass-board laser countermeas	op sure.			
FY 2013 Plans: - Initiate the design of an integrated, miniaturized, form/fit/function bras modularity and open-architecture design principles Design ancillary subsystems (power delivery, thermal management, p	·				
FY 2014 Plans: - Complete the design of an integrated, miniaturized, form/fit/function b subsystem modularity and open-architecture design principles. - Initiate preparations for look-down, shoot-down live-fire testing of the					

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advan	nced Research Projects Agency		DATE: /	April 2013	
400: Research, Development, Test & Evaluation, Defense-Wide PE 0603739E: ADVANCED ELECTRONICS MT-1		PROJEC MT-15: M INTEGRA	IIXED TEC	CHNOLOGY	
B. Accomplishments/Planned Programs (\$ in Millions)		F	Y 2012	FY 2013	FY 2014
- Fabricate, assemble and test ancillary subsystems.					
Title: Diverse & Accessible Heterogeneous Integration (DAHI)			0.000	0.000	17.055
Description: Prior DARPA efforts have demonstrated the ability to mo types to achieve near-ideal "mix-and-match" capability for DoD circuit of Compound Semiconductor Materials On Silicon (COSMOS) program, if freely mixed with silicon complementary metal-oxide semiconductor (Cosmos) (very high speed and very high circuit complexity/density, respectively) (DAHI) effort will take this capability to the next level, ultimately offering devices (for example, Gallium Nitride, Indium Phosphide, Gallium Arse microelectromechanical (MEMS) sensors and actuators, photonic devistructures. This capability will revolutionize our ability to build true "syst volume reductions for a wide array of system applications.	designers. Specifically, one such program was the in which transistors of Indium Phosphide (InP) could CMOS) circuits to obtain the benefits of both technology. The Diverse & Accessible Heterogeneous Integrating the seamless co-integration of a variety of semicondenide, Antimonide Based Compound Semiconductors ices (e.g., lasers, photo-detectors) and thermal manal	pe gies on ductor), gement			
This program has complementary research efforts funded in PE 06011 ELT-01. The Advanced Technology Development part of this program the establishment of an accessible, manufacturable technology for devided materials and devices (including, for example, multiple electronics and CMOS) architectures on a common silicon substrate platform. This parafoundry processes of DAHI technology and demonstrations of advance that leverage heterogeneous integration. By the end of the program, the sustainable DAHI foundry service to be made available (with appropriate laboratory, FFRDC, academic and industrial designers.	n will leverage the 6.1 and 6.2 programs with focus or vice-level heterogeneous integration of a wide array of MEMS technologies) with complex silicon-enabled (art of the program is expected to culminate in accessived microsystems with innovative architectures and dethis effort seeks to establish a technologically mature,	f e.g. ble signs			
FY 2014 Plans: - Develop a high-yield, high-reliability accessible manufacturing process activity providing heterogeneously integrated circuits with at least three design/simulation tool flows necessary to realize the full potential of he - Demonstrate capability for supporting multi-project wafer runs using - Accelerate development of circuit design techniques and methodologic circuit architectures.	e materials/devices. Establish heterogeneous integra eterogeneous microsystems integration. the heterogeneous foundry service under developme	nt.			
Title: FLASH - Scaling Fiber Arrays at Near Perfect Beam Quality			0.000	0.000	13.000

Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ed Research Projects Agency	DATE:	April 2013		
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD)	0: Research, Development, Test & Evaluation, Defense-Wide PE 0603739E: ADVANCED ELECTRONICS MT-1		ROJECT IT-15: MIXED TECHNOLOGY ITEGRATION		
B. Accomplishments/Planned Programs (\$ in Millions)		FY 2012	FY 2013	FY 2014	
Description: The goal of the FLASH program is to demonstrate a high-class beam with near perfect beam quality. To accomplish these ends, of high-power laser weapons while increasing robustness to make it suit aircraft. The completed high-energy laser system will enable long range	it will achieve a 4x reduction in the overall size and weig able for deployment in long-endurance or low-observab				
 FY 2014 Plans: Develop and test a prototype coherently combinable fiber laser with art to the level required for system integration. Demonstrate coherent combining of 100 laser elements. Finish a comprehensive system requirement review of the entire laser power systems, and beam steering. 					
Title: Gratings of Regular Arrays and Trim Exposures (GRATE)		6.208	1.500	0.00	
Description: The goal of the Gratings of Regular Arrays and Trim Expo circuit design methodologies combined with innovative fabrication techn application specific integrated circuits (ASICs) for DoD applications. The layout implementation of circuits by using extremely regular geometries simplified circuit designs will be implemented using high-resolution gratinusing either mask-based or maskless lithography. The methodologies of significantly the design costs of high-performance DoD ASICs at the adviction (CMOS) technology nodes.	iques to enable cost-effective, low-volume fabrication of e design methodologies will enable a simplified physical without sacrificing circuit density or performance. These ng patterns that can be fabricated at high-throughput leveloped in this program are expected to reduce				
 FY 2012 Accomplishments: Demonstrated grating-based design and fabrication of logic/memory "sphotolithography processes. Fabricated analog devices with > 350 GHz performance. Created a design targeted at 14 nanometer technology for CMOS using 		:			
 FY 2013 Plans: Fabricate 1-D digital design at the 14 nm node. Demonstrate > 300 GHz performance for 1-D Silicon Germanium trans- Transition and make the analog 1-D design and fabrication available to 					

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ed Research Projects Agency	DATE:	April 2013		
APPROPRIATION/BUDGET ACTIVITY 0400: Research, Development, Test & Evaluation, Defense-Wide BA 3: Advanced Technology Development (ATD) R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS TECHNOLOGIES NT-15: MIXED TECHNOLOGY INTEGRATION					
B. Accomplishments/Planned Programs (\$ in Millions)		FY 2012	FY 2013	FY 2014	
- Through transition to industry, leverage the knowledge gained from m technology co-optimization at the 10 nm and 7 nm CMOS process node					
Title: Advanced Wide FOV Architectures for Image Reconstruction & Ex	cploitation (AWARE)	16.596	7.613	0.000	
Description: The Advanced Wide FOV Architectures for Image Reconst addresses the passive imaging needs for multi-band, wide field of view ground platforms. The AWARE program aims to solve the technological multi-band camera architectures by focusing on four major tasks: high spitch pixel focal plane array architecture; broadband focal plane array at The AWARE program will advance integration of technologies that enable cameras, including the technologies demonstrated in the related AWAR aggregates the following programs: Lambda Scale (formerly NIRD), Bro DUDE), and Wide Field of View (formerly MOSAIC). The integration of focal plane arrays (FPAs) and cameras. Such focal plane arrays can all persistent surveillance applications.	(FOV) and high-resolution imaging for ground and near I barriers that will enable wide FOV, high resolution and pace-bandwidth product (SBP) camera architecture; small chitecture; and multi-band focal plane array architecture. Ille wide field of view and high resolution and multi-band E program in PE 0602716E, Project ELT-01. AWARE adband (formerly PT-SQUAD), Multi-Band (formerly the technologies will demonstrate subsystems such as				
 FY 2012 Accomplishments: Demonstrated a fully integrated 1280x720, 5 micrometer (μm) pitch lo 120 K. Designed and fabricated 1024x1024, 18 μm Read Out Integrated Circle ambient temperature probe screening tests for short and open circuits. Designed and fabricated 1024x1024, 18 μm broadband detector array fanout circuits demonstrated dark current density of 10^3 A/cm^2 at 200 - Expanded lambda scale detector application space to include Midway operability (99.97 %) from 1280x720, 5 μm pitch MWIR arrays. Also act with f/1.65 optics) from 1280x720, 5 μm pixel arrays. Initiated 6 μm Mercury Cadmium Telluride(HgCdTE) and InGaAs nCB - Transitioned a 12um MWIR handheld target spotting camera into process. 	uit (ROIC) on 8" diameter wafers. ROIC wafers completed as with response from 0.5 to 5 μm. Detectors hybridized to K and 10^6 A/cm^2 at 150 K. e IR (MWIR) and LWIR wavebands. Achieved excellent hieved excellent MWIR NETD (35.5 mK, 35 Hz, @ 110 K in FPA designs for persistent surveillance applications.				
 FY 2013 Plans: Optimize broadband detector array fabrication and assembly processed μm detector arrays to 1024x1024, 18 μm ROICs. Finalize camera integration and demonstrate broadband (0.5 to 5 μm) Fabricate and demonstrate 2048x2048, 5 μm LWIR and MWIR FPAs 	performance with 1024x1024, 18 µm FPA.				

PE 0603739E: *ADVANCED ELECTRONICS TECHNOLOGIES* Defense Advanced Research Projects Agency

UNCLASSIFIED
Page 14 of 16

R-1 Line #55

	UNCLASSIFIED				
Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ced Research Projects Agency		DATE: A	April 2013	
PROPRIATION/BUDGET ACTIVITY 0: Research, Development, Test & Evaluation, Defense-Wide R-1 ITEM NOMENCLATURE PE 0603739E: ADVANCED ELECTRONICS MT-1					
B. Accomplishments/Planned Programs (\$ in Millions)		FY	2012	FY 2013	FY 2014
- Conduct initial field tests for multi-band rifle scope.					
Title: COmpact Ultra-stable Gyro for Absolute Reference (COUGAR)			10.087	0.000	0.000
Description: The COmpact Ultra-stable Gyro for Absolute Reference (of performance potential of the resonant fiber optic gyro in combination will lasers, phase conjugate elements, and silicon optical benches: a compact The COUGAR gyro has a practical and typical size (~ 4 inch diameter) walk), that is more than 100 times better than state-of-the-art gyroscope	th bandgap optical fiber (BGOF), ultra-stable compact act ultra-stable gyro for absolute reference application featuring bias stability and sensitivity (or angle random	S.			
 FY 2012 Accomplishments: Developed bandgap optical fiber realizing >300m lengths of bandgap characteristics. Demonstrated low noise laser suitable for use in COUGAR gyro. Integrated low noise lasers with control electronics to suppress noise Demonstrated an optical bandgap fiber gyro in the laboratory with < 1 	and lock lasers together.	ng			
Title: High Frequency Integrated Vacuum Electronic (HiFIVE)			8.000	0.000	0.000
Description: The objective of the High Frequency Integrated Vacuum Edemonstrate new high-performance and low-cost technologies for imple components. This program developed new semiconductor and micro-fapower amplifiers for use in high-bandwidth, high-power transmitters. Into enable precision etching, deposition, and pattern transfer techniques and electron emitting cathodes for compact high-performance millimete limitations associated with the conventional methods for assembly of high is transitioning via industry.	ementing high-power millimeter-wave sources and abrication technologies to produce vacuum electronic novations in design and fabrication were being pursue to produce resonant cavities, electrodes, and magnet r wave devices. These new technologies will eliminat	ed ics, e the			
FY 2012 Accomplishments: - Completed final fabrication and initial testing of a high-power amplified technologies into a compact module form factor. - Performed laboratory measurements of performance and validate RF - Initiated integration of compact amplifier technology at G-band in a minus of the compact amplifier technology at G-band compact amplifier technology at G-band completed laboratory measurements of performance of miniaturized in the complete description.	power levels, including advanced driver amplifiers. iniaturized tube form factor. d and the nearby radiolocation bands.	ion			
	Accomplishments/Planned Programs Sub	otals	88.667	69.542	86.855

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Exhibit R-2A, RDT&E Project Justification: PB 2014 Defense Advance	ed Research Projects Agency	DATE: April 2013
APPROPRIATION/BUDGET ACTIVITY	R-1 ITEM NOMENCLATURE	PROJECT
0400: Research, Development, Test & Evaluation, Defense-Wide	PE 0603739E: ADVANCED ELECTRONICS	
BA 3: Advanced Technology Development (ATD)	TECHNOLOGIES	INTEGRATION
C. Other Program Funding Summary (\$ in Millions) N/A		
<u>Remarks</u>		
D. Acquisition Strategy N/A		
E. Performance Metrics Specific programmatic performance metrics are listed above in the programmatic performance metrics.	gram accomplishments and plans section.	